

ABSTRACT OF THE DISCLOSURE

A solar cell production method includes the steps of: forming a first electrode layer on a substrate, sequentially forming a p-layer, an i-layer and an n-layer
5 of amorphous silicon on the first electrode layer, and forming a second electrode layer on the n-layer, wherein the i-layer is formed by a plasma CVD method employing plasma discharge caused by application of a pulse-modulated high frequency voltage having a pulse
10 ON time of not longer than 50μ sec and a duty ratio of not higher than 50% to improve a photo-electric conversion efficiency of the solar cell.